



Manitou Systems Inc.



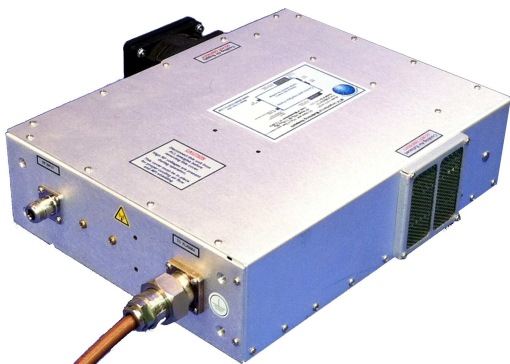
SERIES MTK MANUAL MATCHING NETWORK

- MANUALLY CONTROLLED
- HIGH POWER AND LOW POWER MODELS
- DC BIAS PROBE & METERING
- FORCED AIR COOLED
- MANY IN/OUT CONNECTOR OPTIONS
- FLAT DESIGN FOR EASY MOUNTING

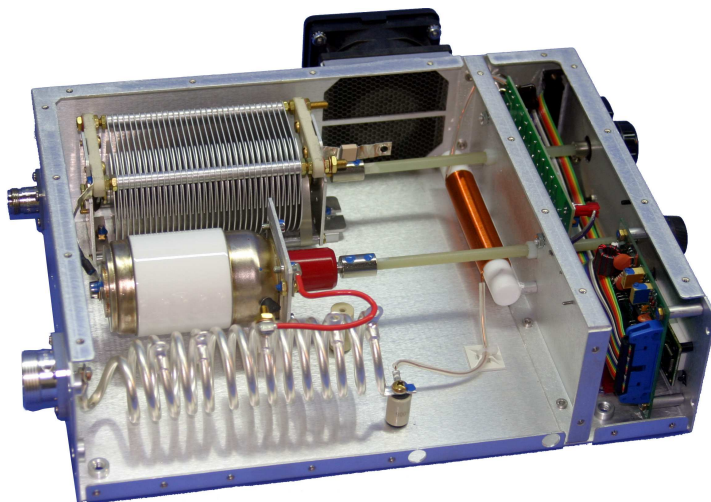
The **Series MTK™** impedance matching network is specifically designed for continuous operation in gas plasma process applications. It will provide an impedance match between the plasma and the RF generator's 50 ohm output. All MTK models are manually controlled, fan cooled and include a silver plated, adjustable series inductor. High quality variable capacitors ensure high reliability and power transfer efficiency.

The Series MTK is available in standard and custom versions to accommodate use with all types of magnetron sputtering sources, capacitive plasma electrodes and inductive plasma sources. Options include: DC bias or RF current metering, air gap or vacuum variable capacitors, various industry standard coaxial connectors and special matching circuit configurations.

These images show a typical unit that includes a DC Bias probe, digital LED metering, tapped series inductor and, additional fixed shunt capacitors. The RF input connector is a type N female while the output to the plasma is a type 7/16 DIN female.



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Represented by:

Manufactured in the USA



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*Technical specifications are subject to change without prior notice.
See our web site or contact us directly for the latest specifications and pricing.*

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